

Amendments to the Claims

1-16. (Cancelled)

17. (Currently amended) A low-reflective thin-film substrate comprising:
a single thin film formed ~~in multilayer~~ of a plurality of layers on a transparent glass substrate,
wherein the thin film contains no chromium component and comprises an alloy of Ni and at least one of Fe, Mo, W and Cu,
and wherein the low-reflective thin-film substrate has a ~~minimum~~ reflectivity which is 0.5% or lower and an optical density of at least 4 at a wavelength in the visible light region.

18. (Previously presented) The low-reflective thin-film substrate of claim 17, wherein the thin film is formed by sputtering under a gas atmosphere of at least one of an inert gas, an oxygen gas, and a carbon oxide gas in a vacuum film-forming apparatus.

19. (Currently amended) The low-reflective thin-film substrate of claim 17, wherein the thin film further contains at least one of ~~Cu~~, Ti, Zr and Sn.

20. (Currently amended) The low-reflective thin-film substrate of claim 18, wherein the thin film further contains at least one of ~~Cu~~, Ti, Zr and Sn.

21-24. (Cancelled)

25. (Currently Amended) The low-reflective thin-film substrate of claim 17, wherein each layer in said plurality of layers ~~forming the multilayer have~~ has different optical properties from one another.